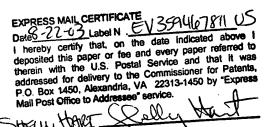
Attorney Docket No. 008401 03





Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

In re Application of: Kenneth S. Collins, Hiroji Hanawa, Kartik Ramaswamy, Andrew Nguyen, Amir Al-Bayati, Biagio Gallo, and Gonzalo Antonio Monroy

Entitled: PLASMA IMMERSION ION IMPLANTATION APPARATUS
INCLUDING A CAPCITIVELY COUPLED PLASMA SOURCE HAVING
LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE

Attorney Docket No.: 008401 03

Sir:

Enclosed herewith for filing is a patent application entitled PLASMA IMMERSION ION IMPLANTATION APPARATUS INCLUDING A CAPACITIVELY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE including 139 pages of specification, 58 claims and abstract, and 85 sheets of drawings (Figures 1-112).

This application is being filed missing parts and specifically without a declaration by the inventors and without a filing fee. The application is being filed in the names of the inventors, Kenneth S. Collins, Hiroji Hanawa, Kartik Ramaswamy, Andrew Nguyen, Amir Al-Bayati, Biagio Gallo, and Gonzalo Antonio Monroy.

Please address all correspondence to:

Patent Counsel, M/S 2061 Legal Affairs Dept. Applied Materials, Inc. P.O. Box 450-A Santa Clara, CA 95035

Please direct all telephone inquiries to: Robert M. Wallace (805) 644-4035

Dated: August 22, 2003

Respectfully submitted,

Robert M. Wallace Reg. No. 29,119

Attorney for Applicant(s)